

Technology Overview

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NCD – Master MIRI



Modular Characterization

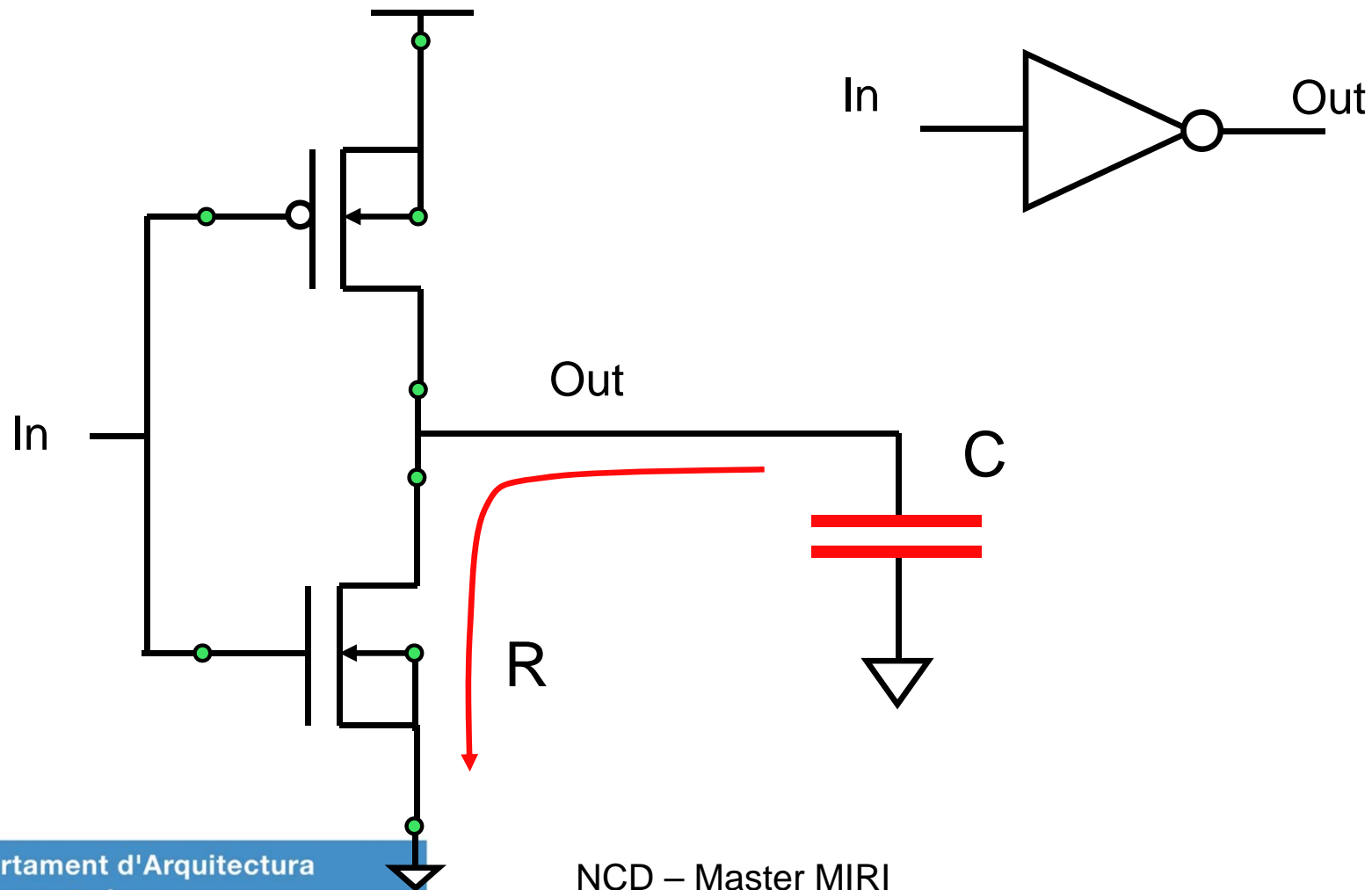
- It is impossible to analyze a million transistor circuit looking at every single transistor
- Modular approach makes it feasible
- Grouping transistors in gates, gates in blocks and so on.
- Keys to the analysis of MOS circuits:
 - The behavior depends on the input values.
 - Interface parameters: capacity of the inputs/outputs and impedance of the outputs
 - Transmission gates are a different story.

Modular Characterization

- Elements that define a module:
 - Logic function
 - Capacity of the inputs (~ gate capacity of the transistors)
 - Capacity of the outputs (~ drain capacity of the output transistors)
 - Impedance of the outputs
 - Internal propagation time
- Capacity and impedance are fixed parameters
- Internal propagation time depends on the inputs:
 - Characterize the highest/lowest times
 - Characterize depending on functionality (e.g. ALU), statistical or sampling (e.g. FU inputs), etc.

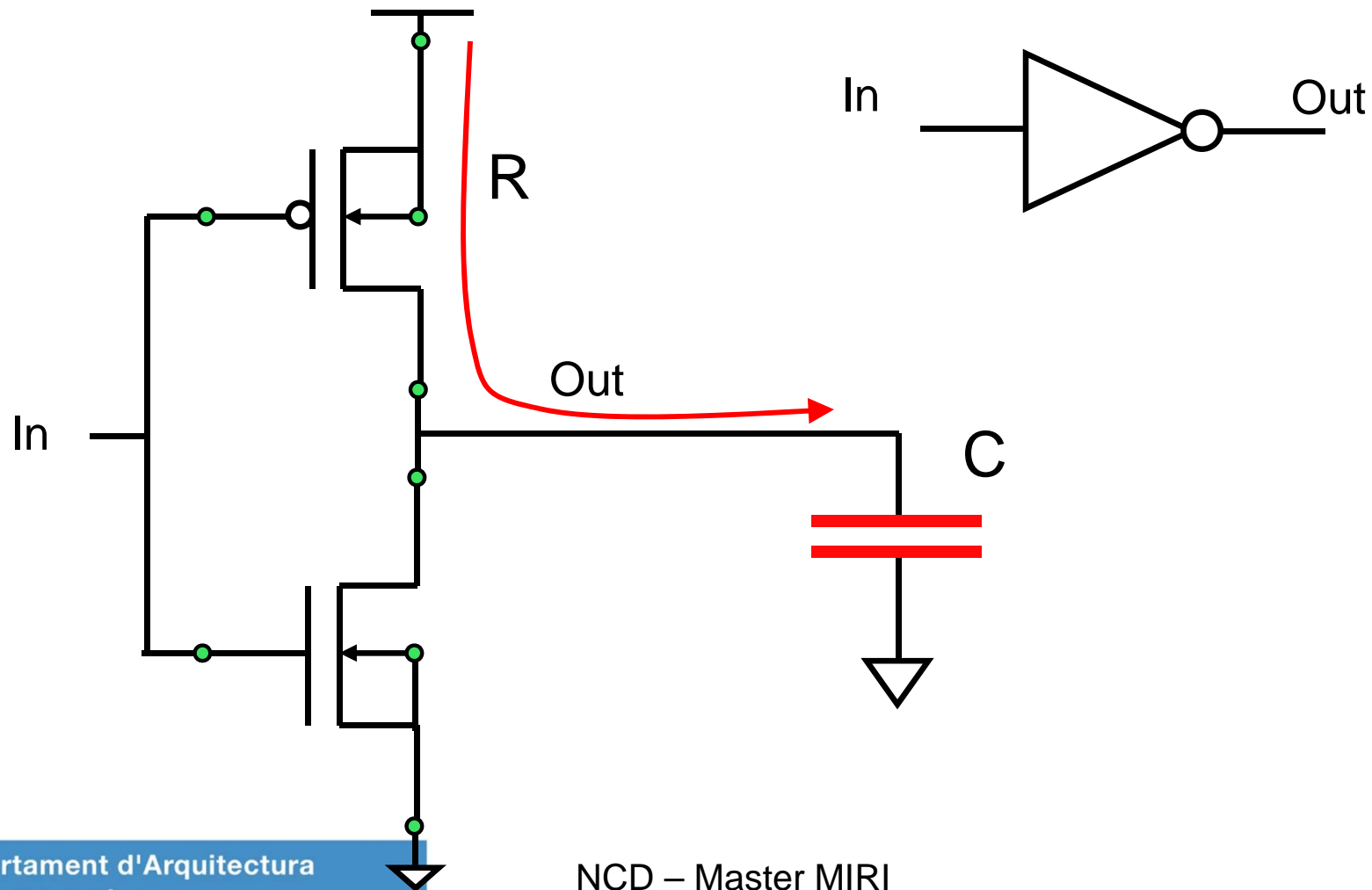
MOS gate delay

- Delay depends on RC relationship:



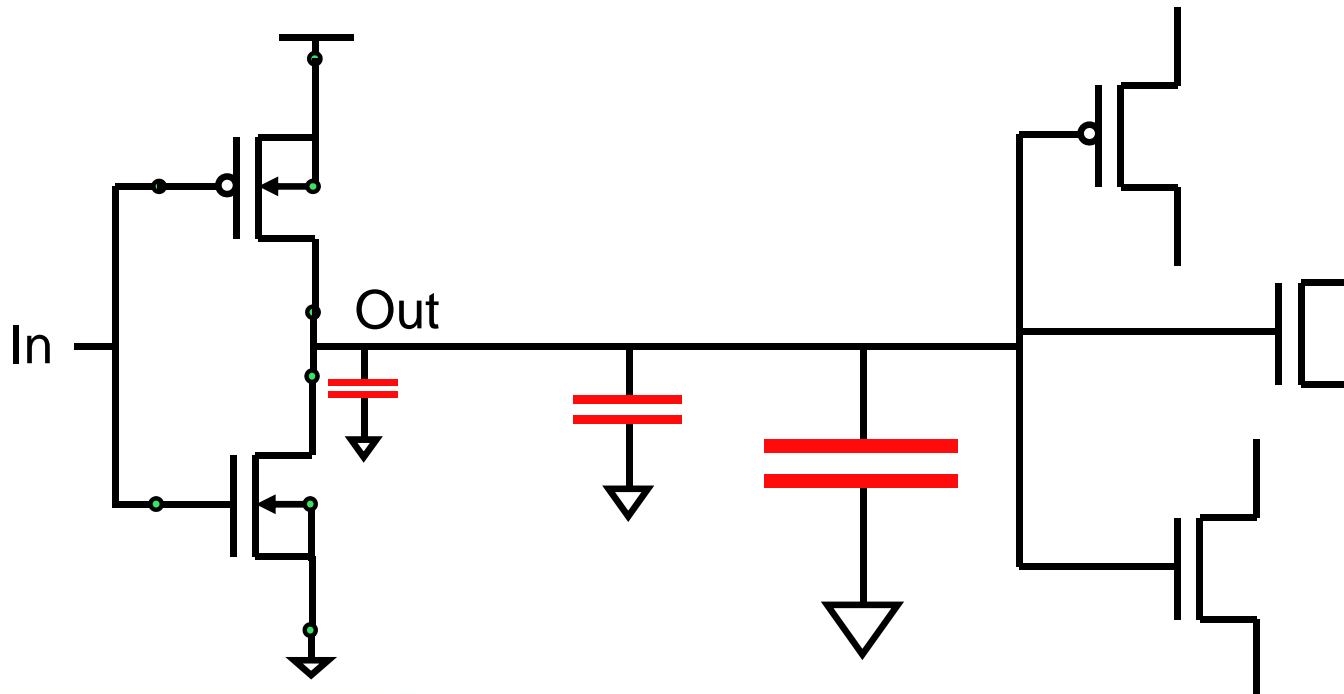
MOS gate delay

- Delay depends on the RC relationship:



MOS gate delay

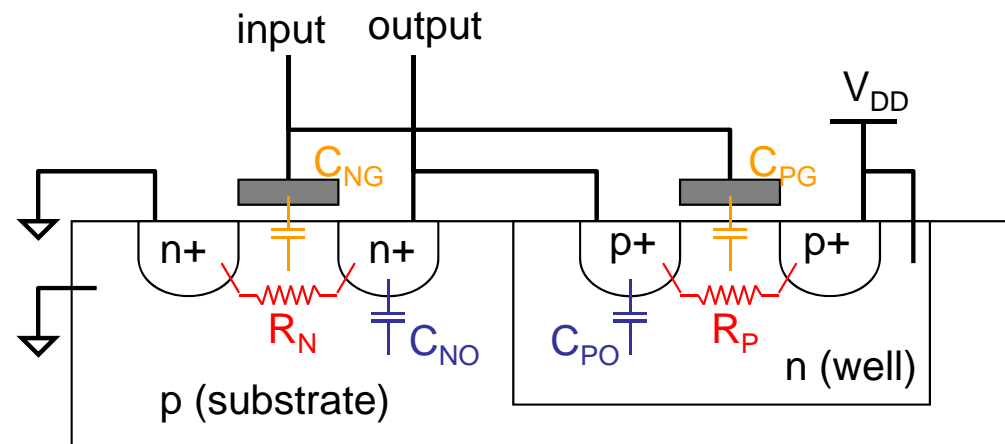
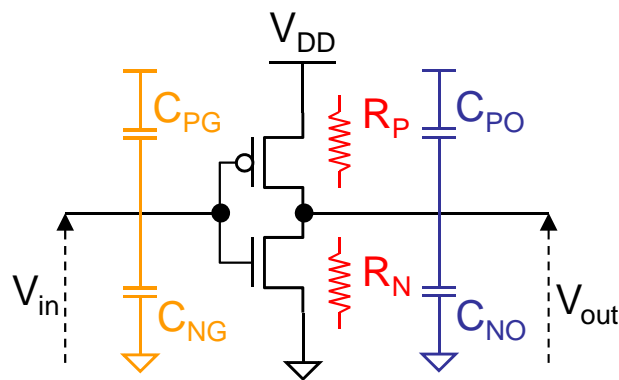
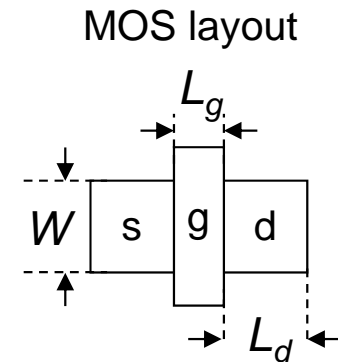
- The capacity C depends on:
 - Capacity of the difussions of the output nodes
 - Capacity of the connections
 - Capacity of the nodes connected to the output



MOS gate delay

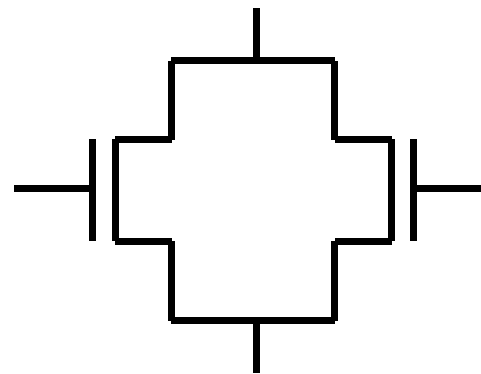
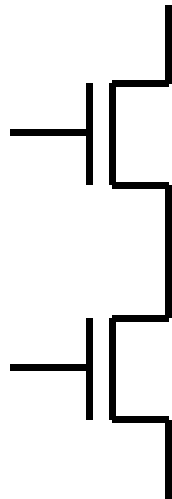
INV device model

- R_N, R_P : ON-resistance of nMOS / pMOS
→ Proportional to L_g / W
 - C_{NG}, C_{PG} : Gate capacitance of nMOS / pMOS
→ Proportional to $L_g \cdot W$
 - C_{NO}, C_{PO} : Drain capacitance of nMOS / pMOS
→ Proportional to $L_d \cdot W$ and $L_d + W$
- *In reality, R_N, R_P, C_{NO}, C_{PO} are not constant, but dependent on the voltages at the gate and drain*



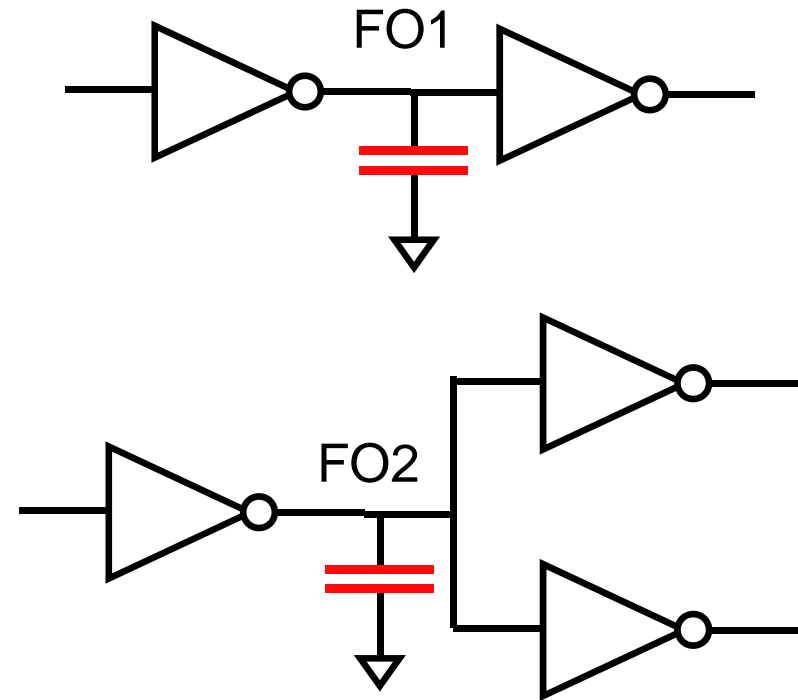
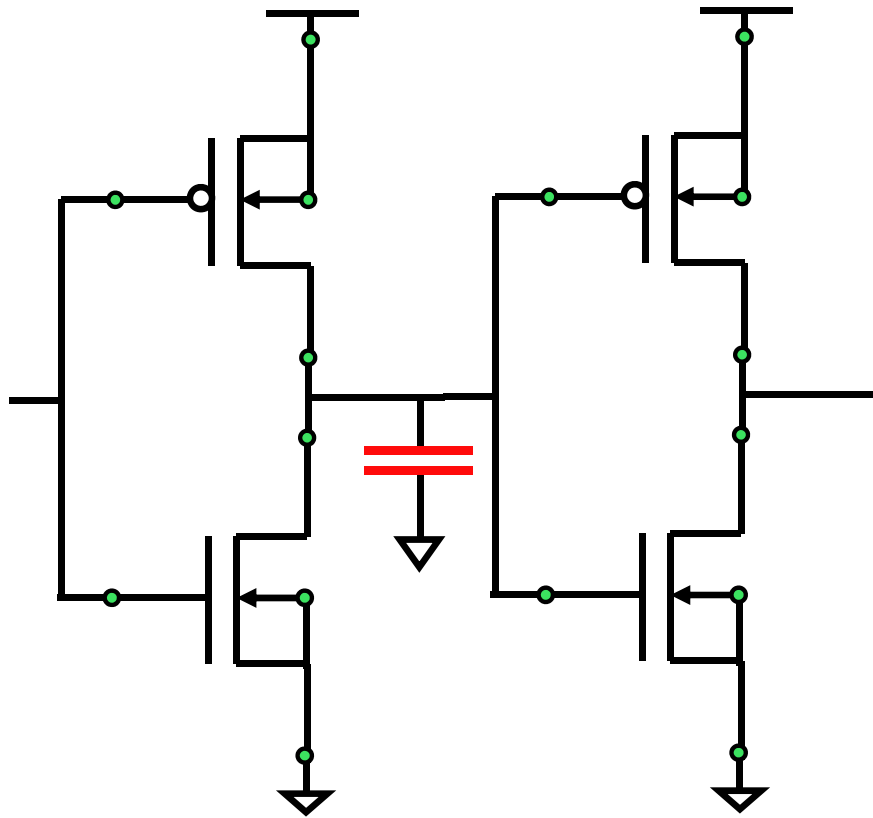
MOS gate delay

- The resistance R depends on:
 - Dimensions of the transistors that charge/discharge the output capacity ($\sim L/W$).
 - Transistors in a row add resistance: L_1/W_1 L_2/W_2
 - $R \sim L_1/W_1 + L_2/W_2$
 - Transistors in parallel reduce resistance: L_1/W_1 L_2/W_2
 - $R \sim 1 / (1/(L_1/W_1) + 1/(L_2/W_2))$



MOS gate delay

- FO1 (Fan Out of 1) is defined as the delay of an inverter connected to another inverter of equal sizes
 - FO2 is equivalent to connecting two inverters, etc.

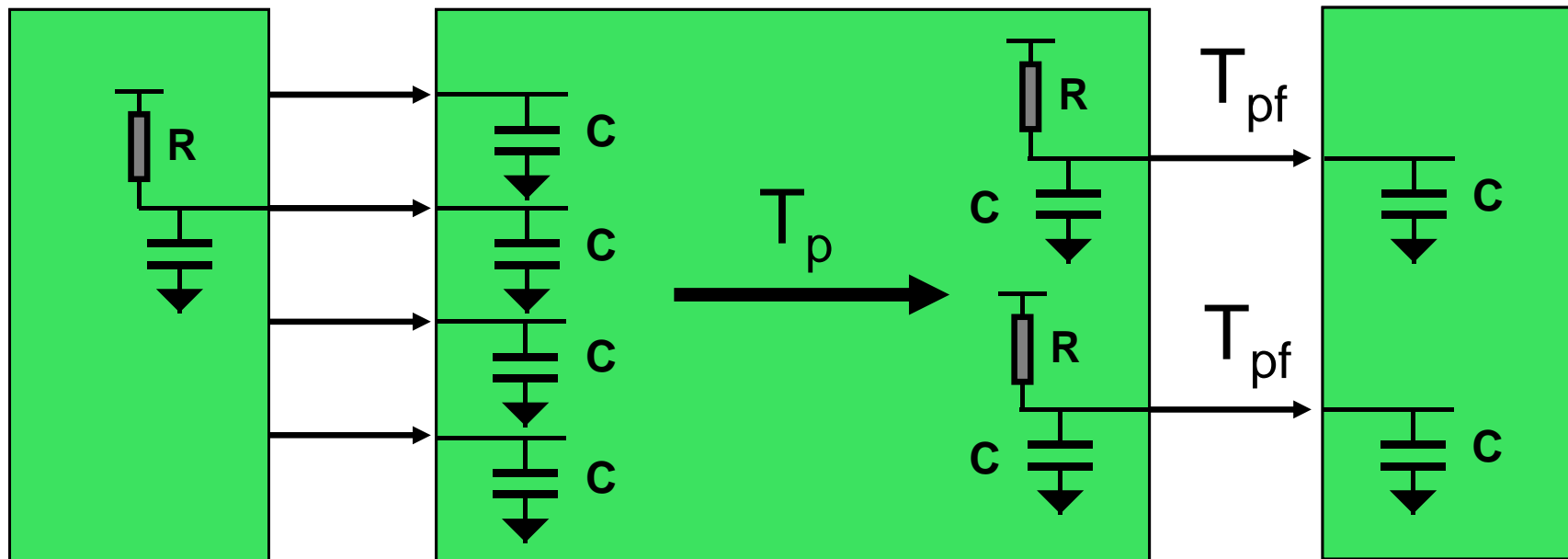


Characterization elements

- Module parameters:
 - Capacity of the inputs:
 - Capacity of the outputs:
 - Impedance of the outputs.
 - Charge-dependant propagation time:
 - Internal propagation time:

C_I
 C_O

T_{pf}
 T_p



Example: characterization of a NAND

- Parameters of the gate **NAND2**

- Input Capacity:

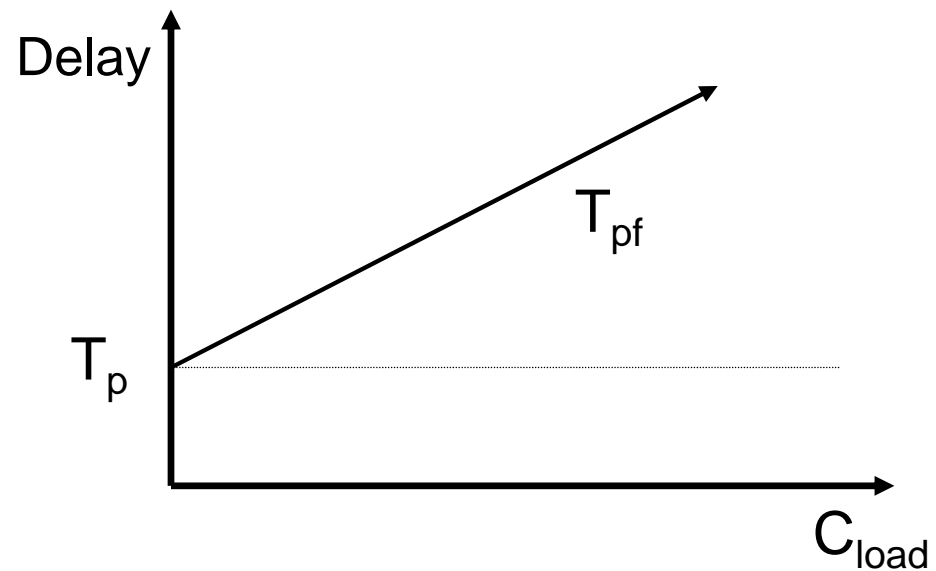
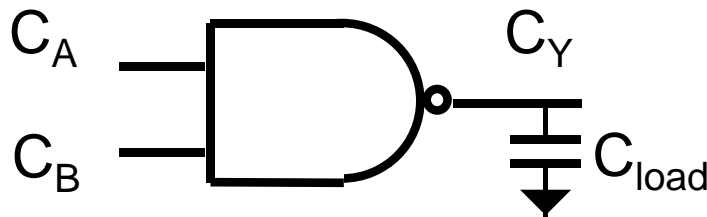
C_{I-A} C_{I-B} 40 fF

- Output Capacity :

C_{O-Y} 25 fF

- Propagation times:
 Charge-dependant:
 Internal:

$T_{pf Y}$ 0.02 ns/fF
 $T_{p Y}$ 1 ns



Example: characterizing an inveter

- Parameters of the gate: **INV**

- Input Capacity:

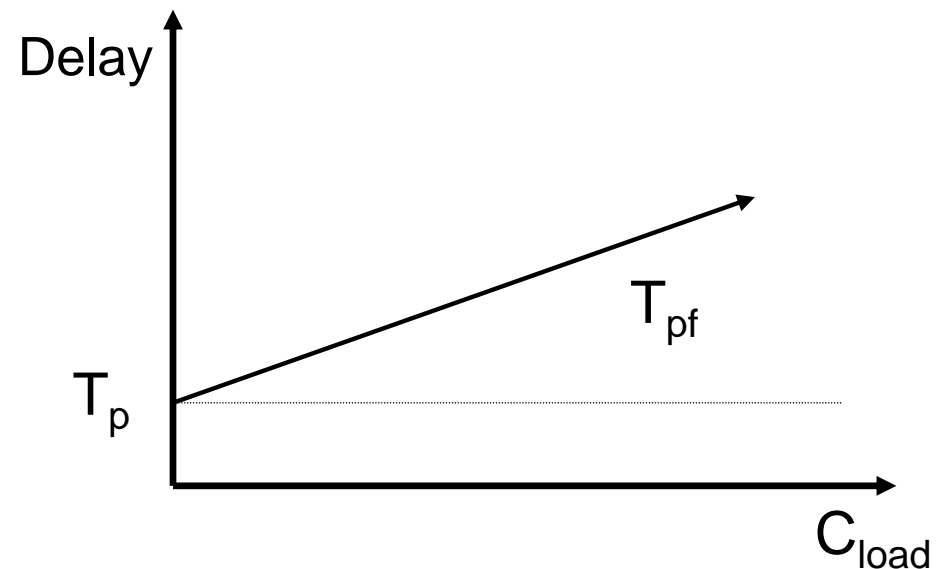
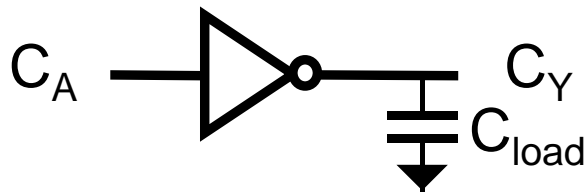
C_{I-A} 30 fF

- Output Capacity:

C_{O-Y} 25 fF

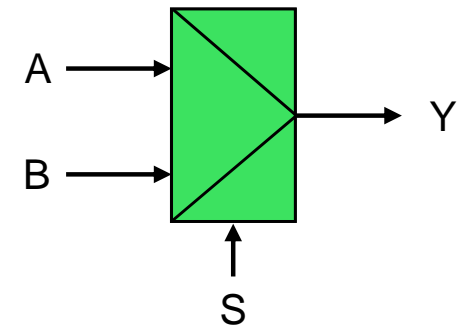
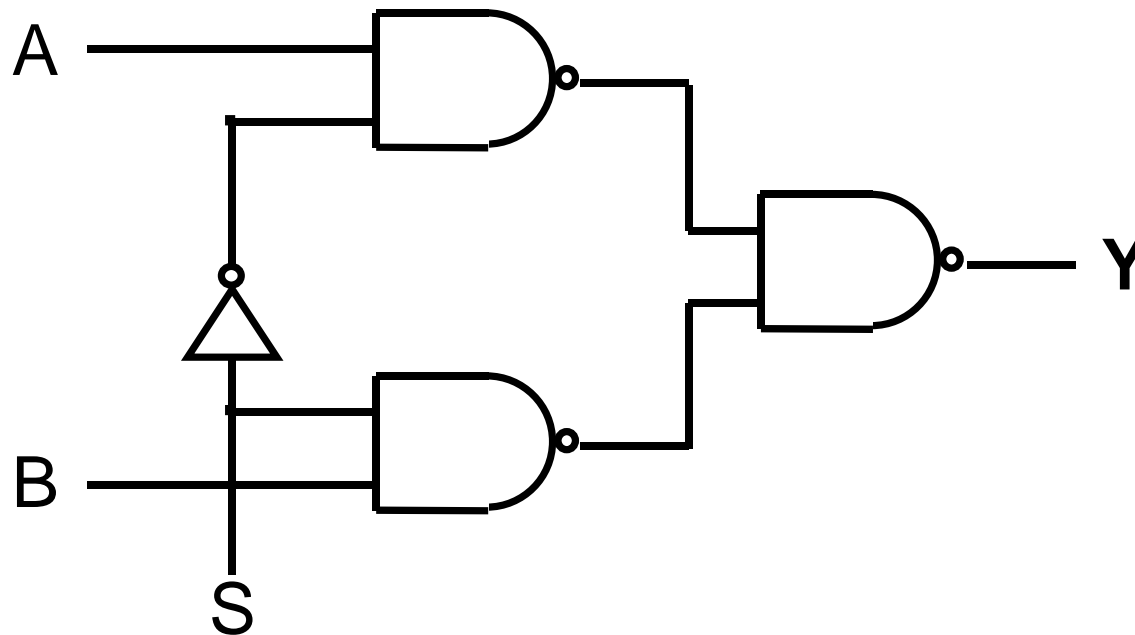
- Propagation times:
Charge dependant:
Internal:

$T_{pf Y}$ 0.01 ns/F
 $T_{p Y}$ 0.8 ns



Example: characterization of a MUX

- We can analyze the MUX with both previous gates (NAND and INV):
 - **Simplicity**: we use/generate the same parameters
 - **Conservative analysis**: we introduce some error.



Capacity Characterization

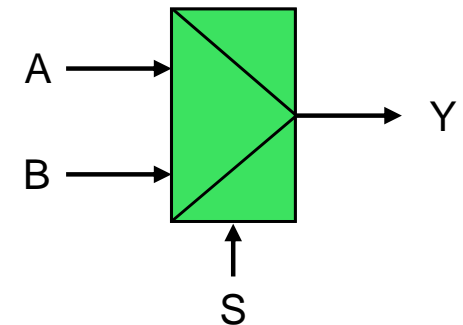
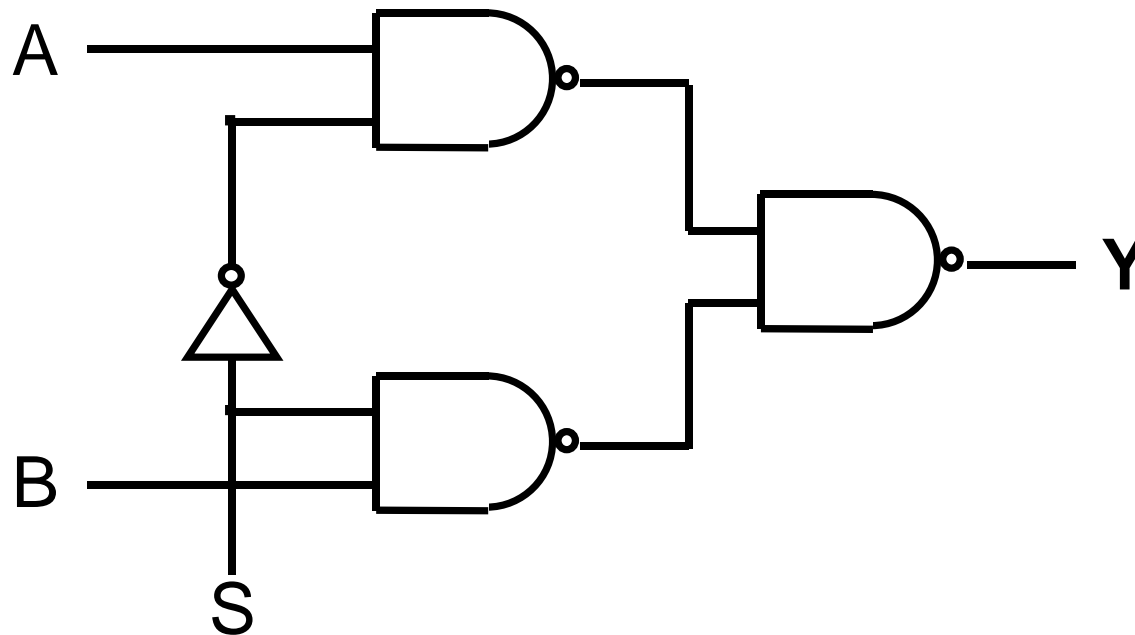
- Capacities:

- $C_A = C_{I-NAND} = 40\text{fF}$

- $C_S = C_{I-NAND} + C_{I-NOT} = 70\text{fF}$

$$C_B = C_{I-NAND} = 40\text{fF}$$

$$C_Y = C_{O-NAND} = 25\text{fF}$$



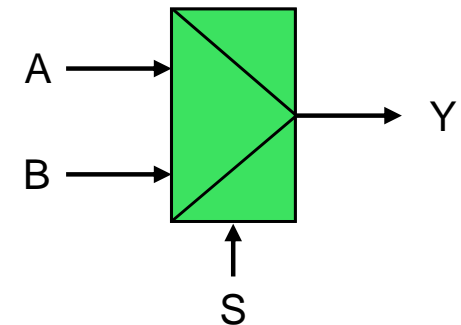
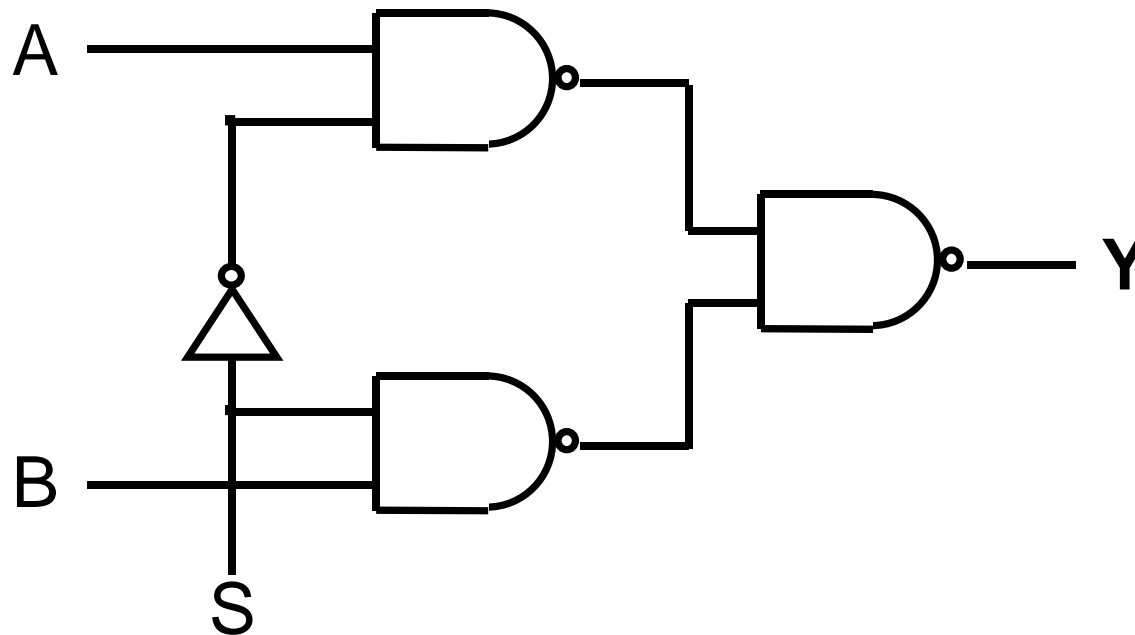
Characterization of the T_{pf}

- Charge dependant propagation time:

- $T_{pf Y} = T_{pf NAND} = 0.02ns/fF$

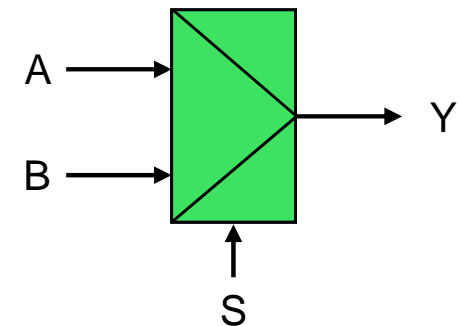
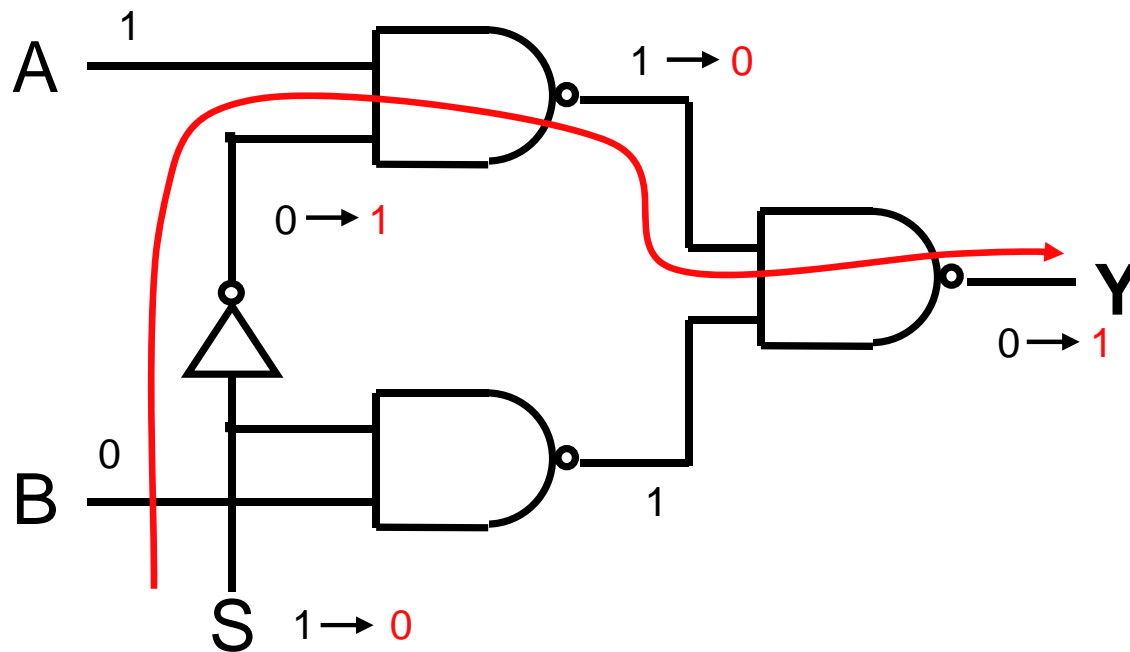
- Separating charge/discharge:

$$T_{pf Y+} = T_{pf NAND+} \quad T_{pf Y-} = T_{pf NAND-}$$



Characterization of the critical Tp

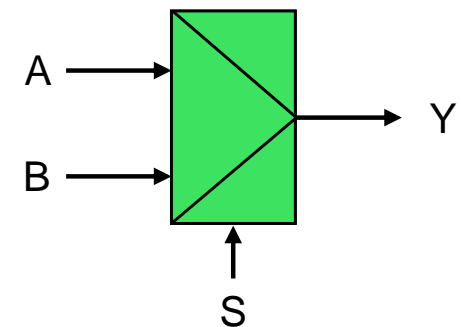
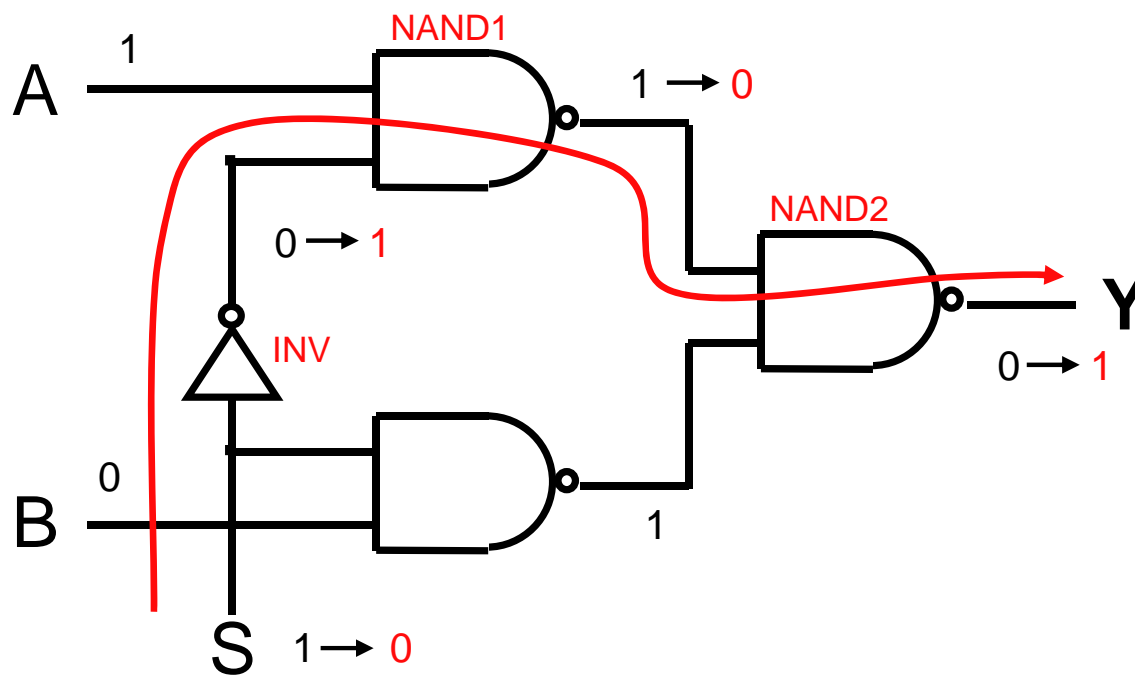
- Internal propagation time:
 - Depends on the critical path: slowest path between one input and the output of the circuit.
 - It MUST exist (the combination of inputs is feasible)



Characterization of the critical T_p (cont.)

- Maximum (critical) propagation time calculation:

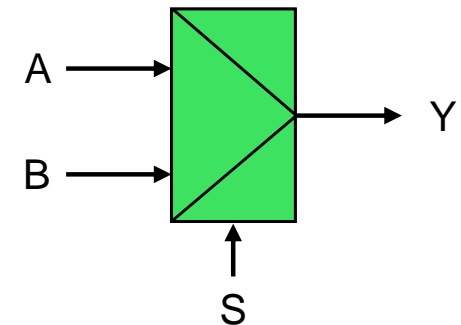
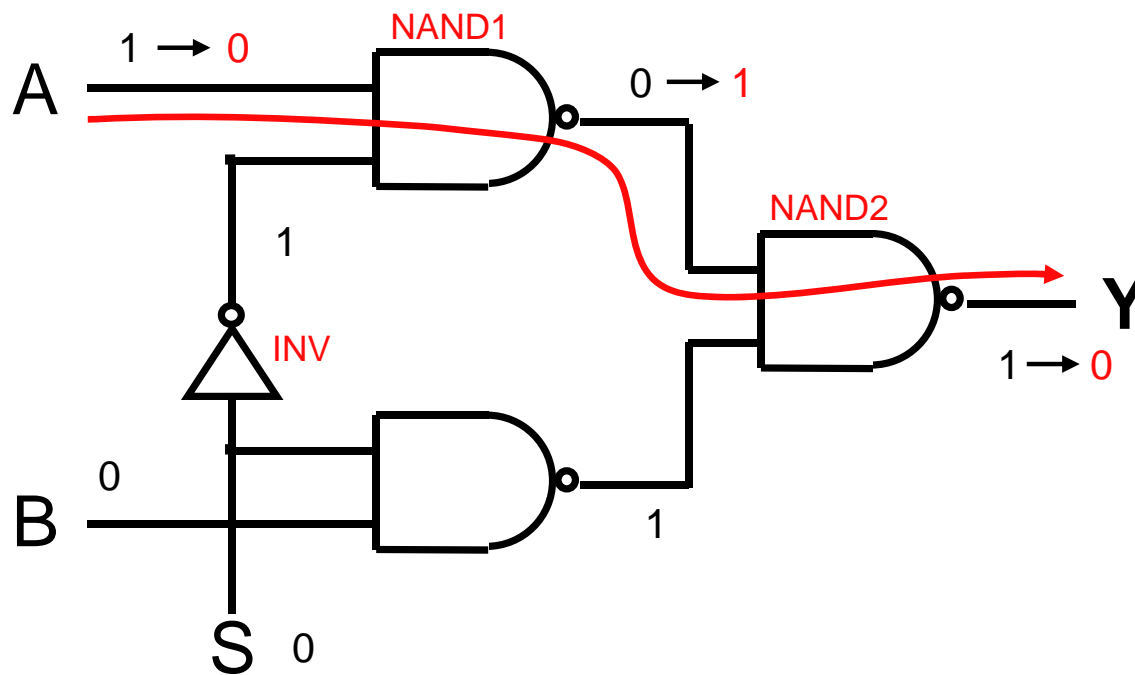
$$- T_{pY} = T_{pINV} + T_{pfINV} C_{I-NAND1} + T_{pNAND1} + T_{pfNAND1} C_{I-NAND2} + T_{pNAND2}$$



Characterization of the minimum T_p

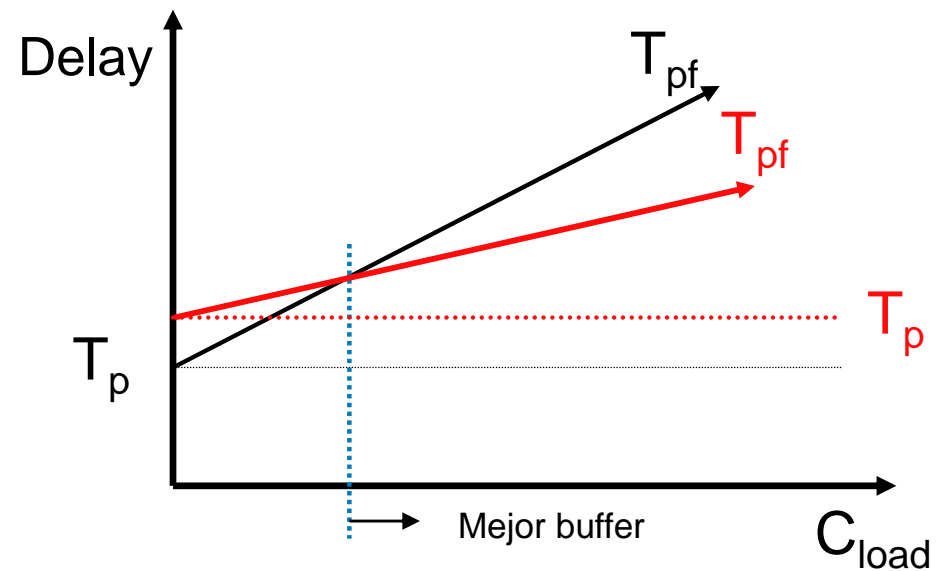
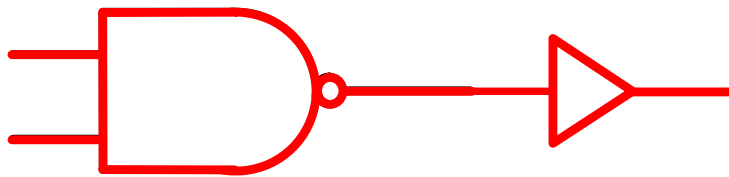
- Minimum propagation time calculation :

$$- T_{pY} = T_{p\text{NAND1}} + T_{pf\text{NAND1}} C_{I\text{-NAND2}} + T_{p\text{NAND2}}$$



Buffers for better performance

- The delay of a component depends on its propagation time, but ALSO depends on its connection.
- We can increase overall performance by trading off T_p to reduce the T_{pf} .



Conclusions

- MOS technology allows a *modular analysis*.
- A system can be characterized with a set of parameters.
- Charge-dependant propagation times T_{pf} just depend on the output transistors.
- Buffers in the output *rise* the T_p , but *reduce* the T_{pf} .
- When considering the propagation time, there exists a high and a low, but it may not be the value we want (e.g. in a Ripple Carry Adder):
 - Critical T_p is proportional to the number of bits.
 - Usually just 4-5 bits generate carry.